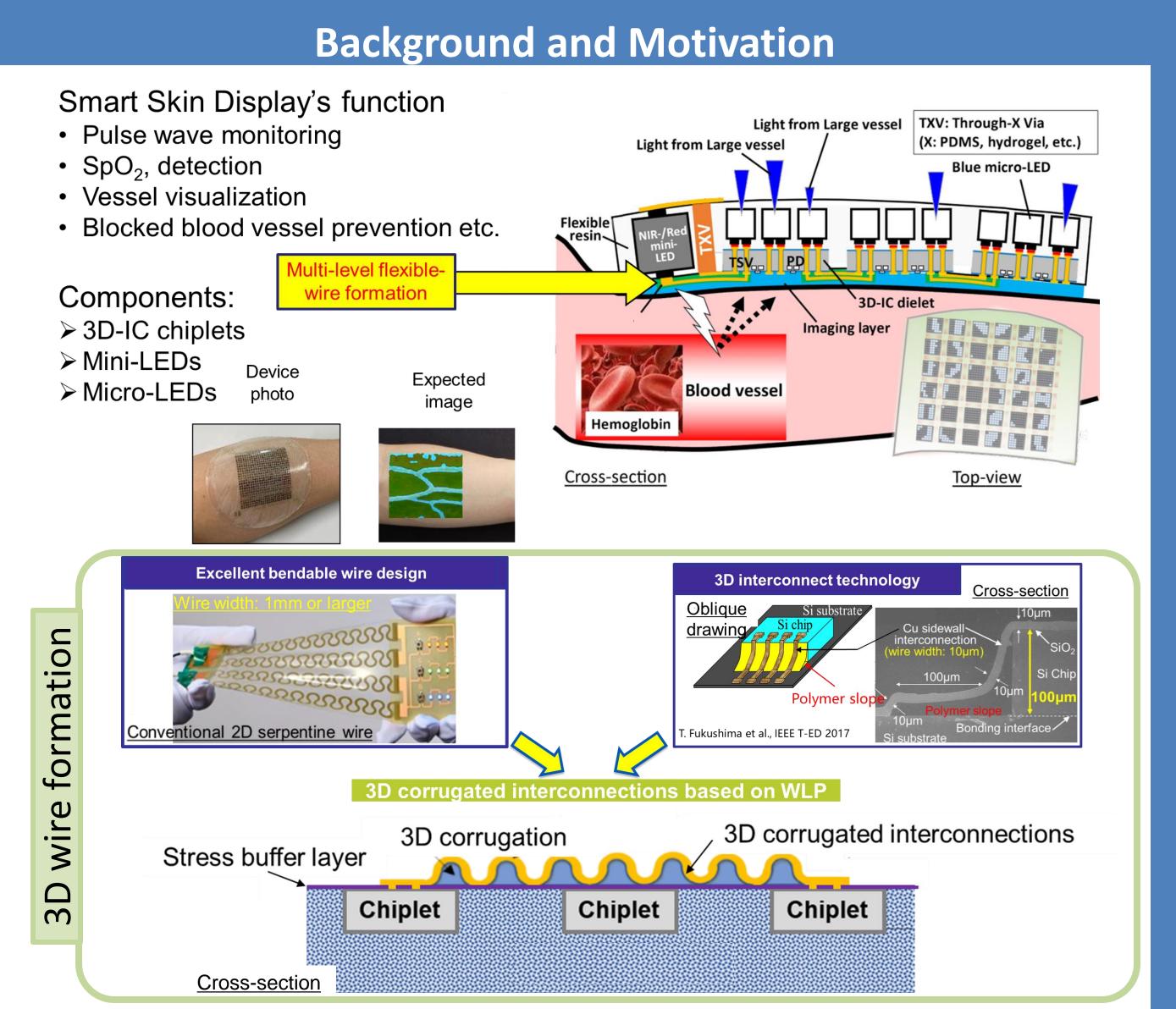
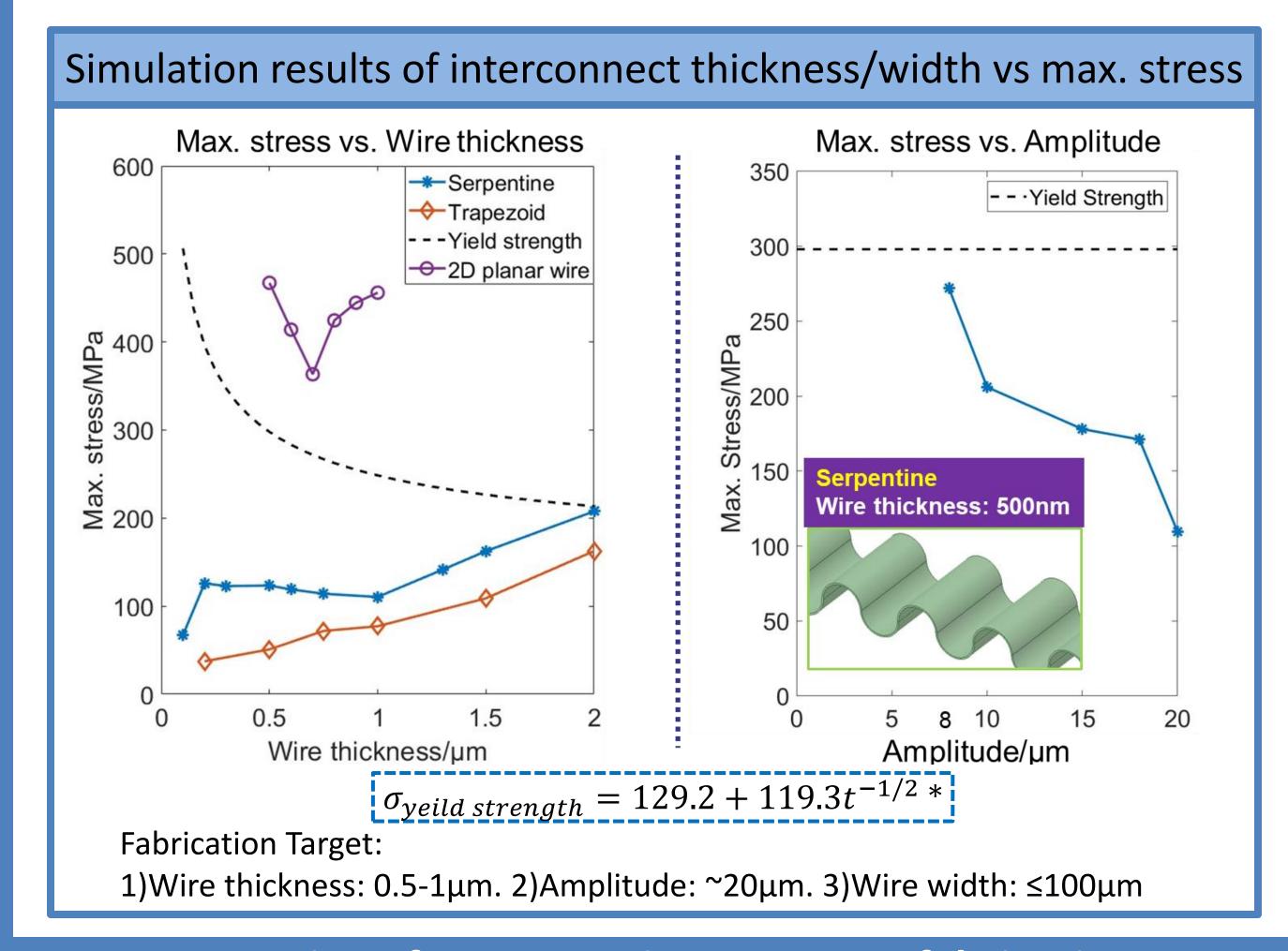
High-Bendable 3D Corrugated Interconnections for Chiplet-Embedded Flexible Hybrid Electronics (FHE) Using Wafer-Level Packaging

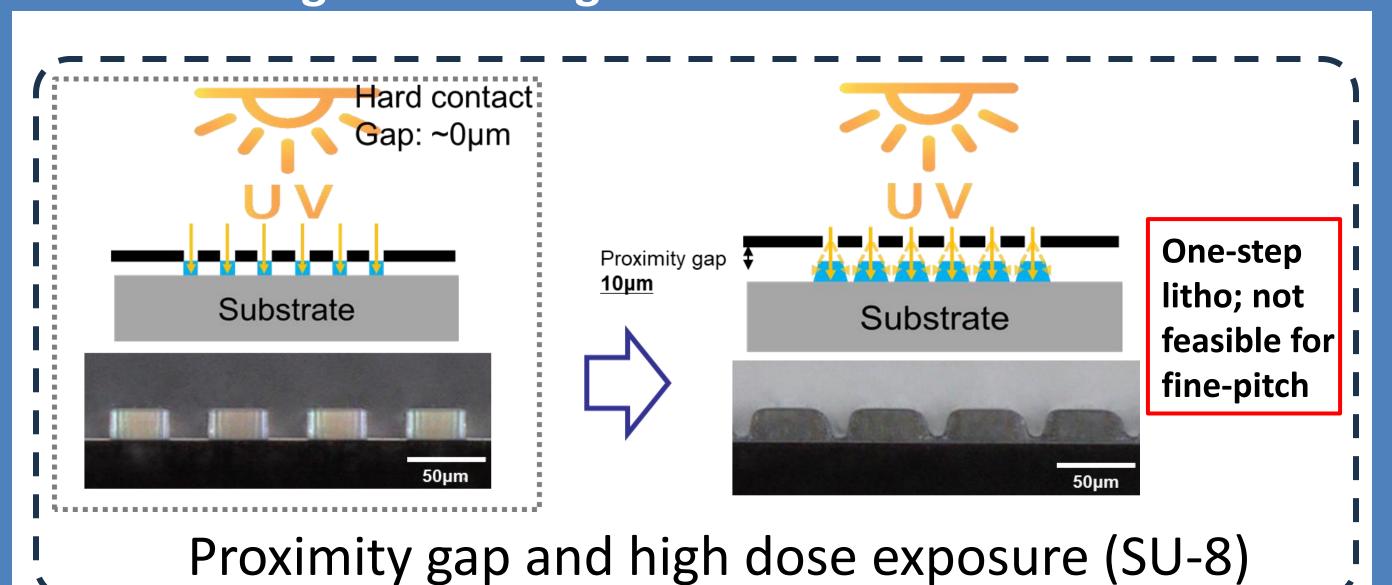
Chang Liu, Tadaaki Hoshi, Jiayi Shen, Atsushi Shinoda, Zehua Du, Hisashi Kino, Tetsu Tanaka, and Takafumi Fukushima Tohoku University

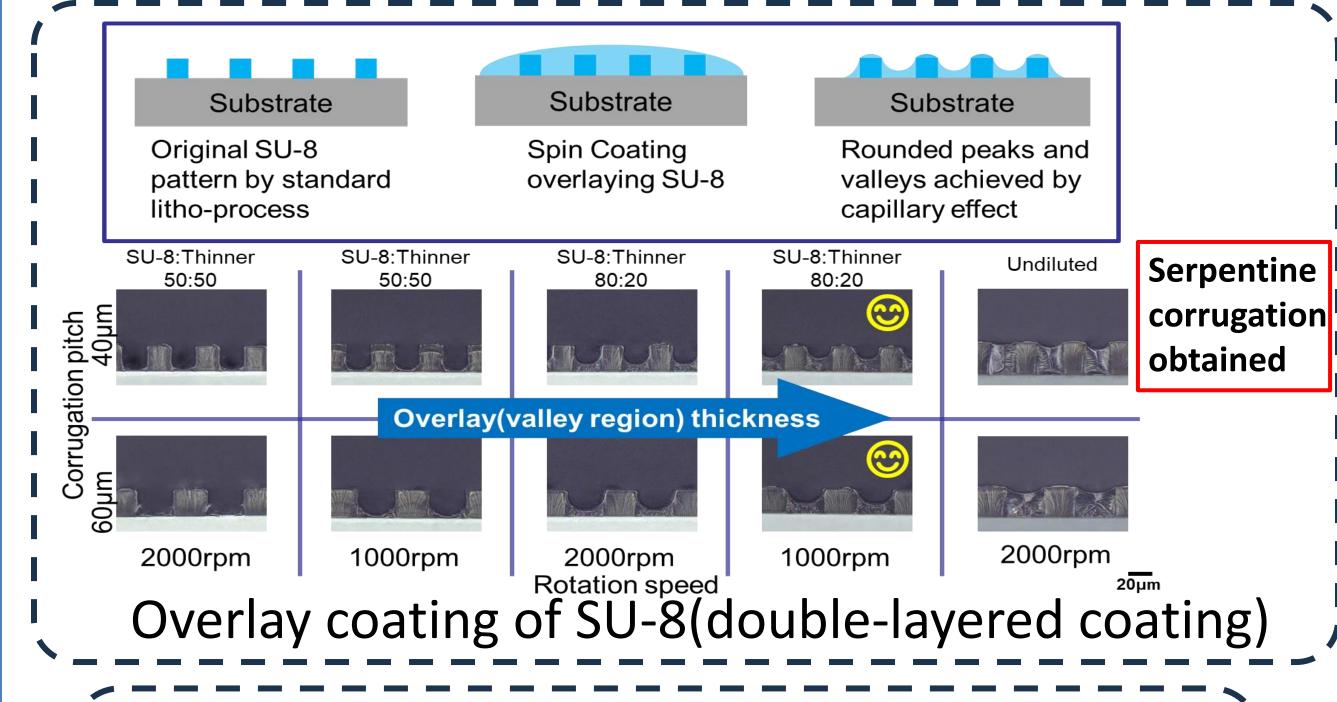


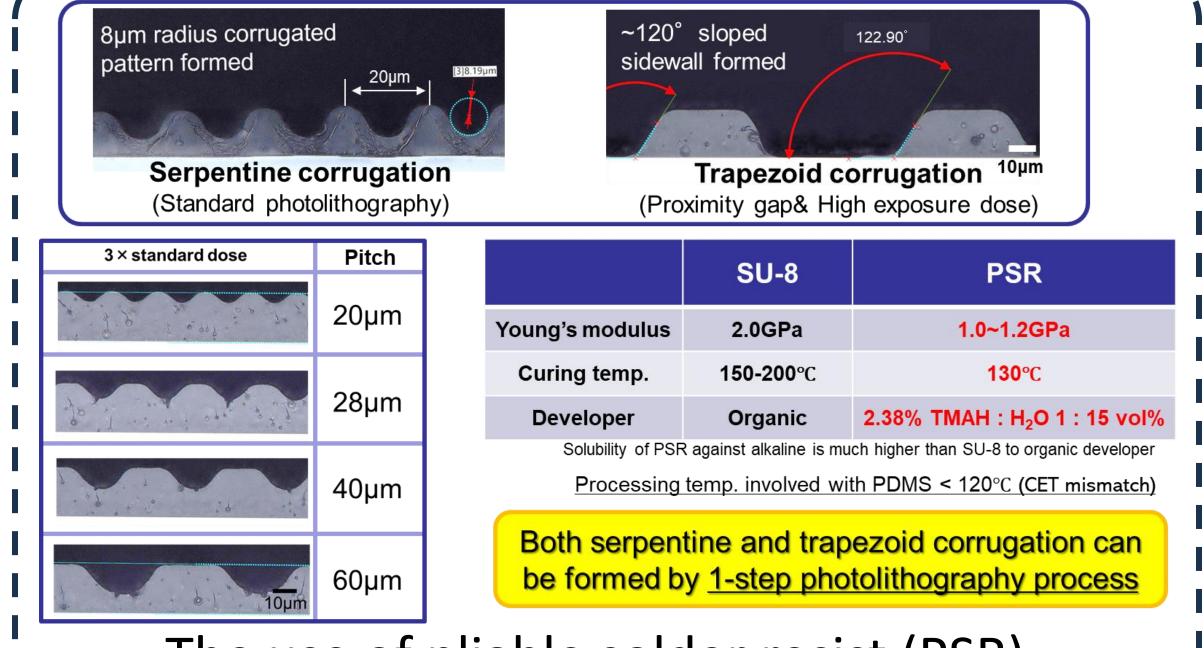
Simulation Result



Strategies of corrugate interconnect fabrication







The use of pliable solder resist (PSR)

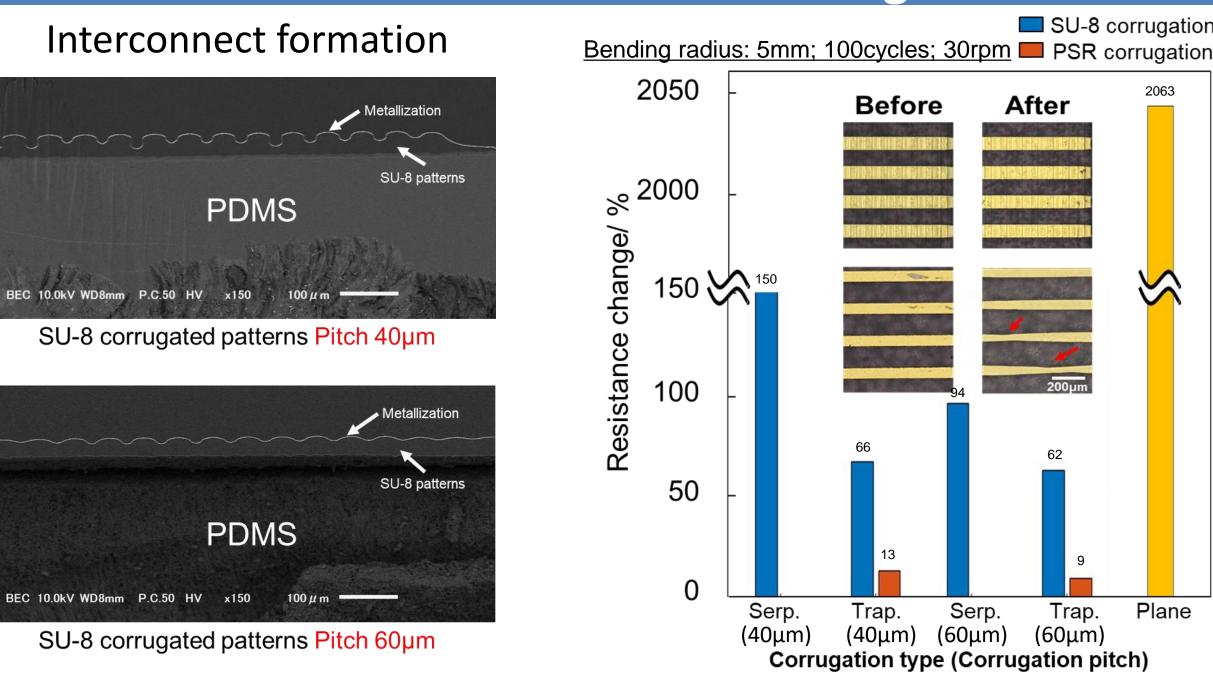
Fabrication Result and Bending Test

■ SU-8 corrugation

After

Trap.

(60µm)



Conclusion

- To address the interconnect bending stress concentration issue, three strategies were proposed to form 3D corrugated structures.
- Two photosensitive materials, brittle SU-8 and flexible PSR, are employed for the fabrication of corrugations. PSR costs less effort but requires more exploration.
- The resistance changes are drastically reduced when using the 3D corrugated wires compared to the wires without the 3D corrugation.
- PSR trapezoid corrugation further reduced the resistance change due to its lower Young's Modulus.

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